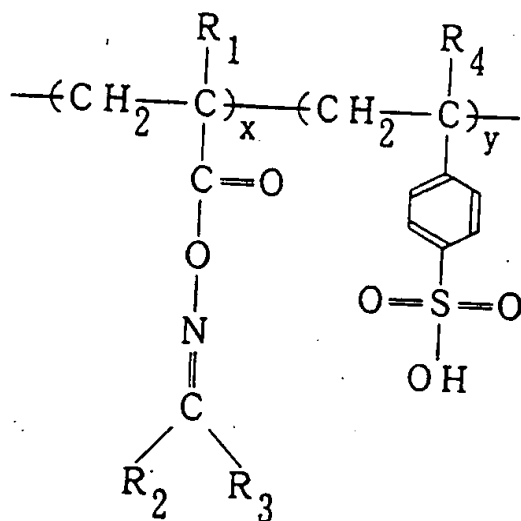


1. (Amended) A pattern forming material comprising a copolymer including a first group for generating a base through irradiation with an energy beam and a second group having an acidic property;

wherein said copolymer is a binary copolymer represented by the following general formula or a ternary or higher copolymer obtained by further polymerizing said binary copolymer with another group:



wherein R_1 indicates a hydrogen atom or an alkyl group; R_2 and R_3 independently indicate a hydrogen atom, an alkyl group, a phenyl group or an alkenyl group, or together indicate a cyclic alkyl group, a cyclic alkenyl group, a cyclic alkyl group having a phenyl group or a cyclic alkenyl group having a phenyl group; R_4 indicates a hydrogen atom or an alkyl group; x satisfies a relationship of $0 < x < 1$; and